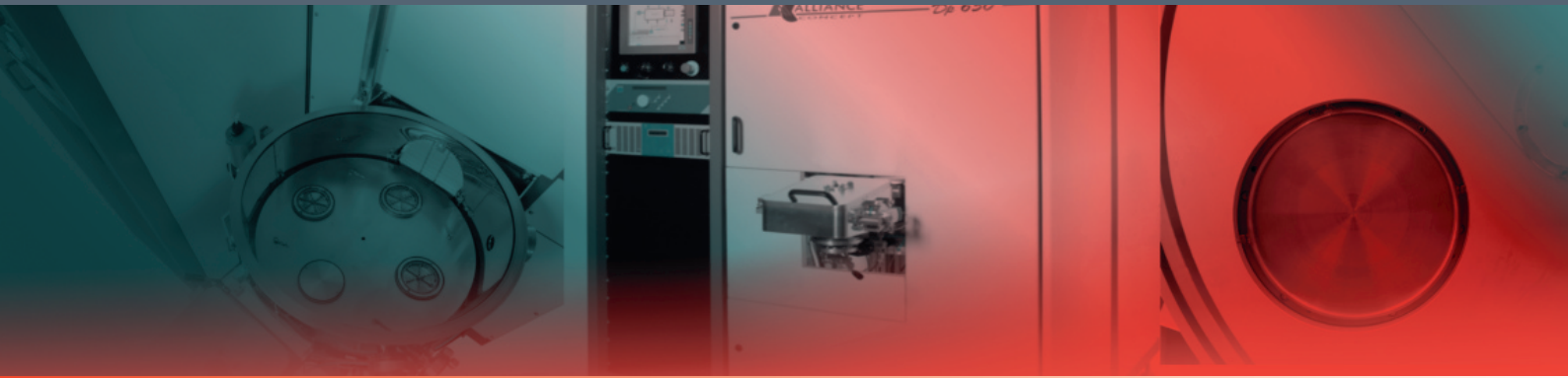


Vacuum ▶ PVD Thin films ▶ Leak testing ▶ Plasma



Thin film PVD sputtering system for 200 mm substrate

DP1100



by

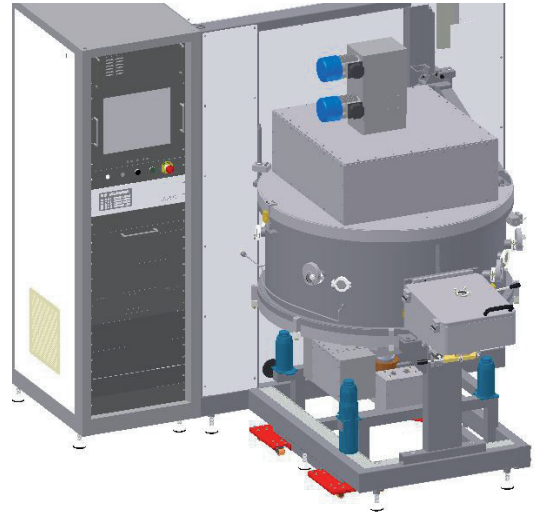
allianceconcept

Modular and evolutive system for multi layers and materials deposition

Versatile equipment, the DP1100 has a chamber diameter of 1100 mm. This volume can accommodate for example **four 250 mm diameter sources or four 300 mm**.

Benefiting from joint development of our sputtering system product line, the DP1100 is currently our flagship product. We have supplied over forty systems around the globe, and as such, it is the spearhead of the PVD product range. Either developed for industrial applications and R&D themes, DP1100 is the right tool.

"The hallmarks of this best-seller are reliability, robustness and moreover, cost effectiveness."



Main features

Vacuum chamber diameter :	1100 mm
Height :	480 mm
Volume :	About 350 litres
Ultimate vacuum (turbomolecular configuration) :	5.10^{-7} mbar ^[1]
Ultimate vacuum (cryogenic configuration) :	5.10^{-8} mbar ^[1]
System throughput :	4 active 300 mm position
Planar configuration uniformity :	< +/- 5% ^[1]
Through the wall installation :	Yes
Load lock :	Yes
Fully automatic system controller :	- Process management - Traceability

^[1] These values have been measured on equipment we have delivered and should be handled as information only. The features of a system depend on its final configuration.

